PATENT COOPERATION TREATY

From the INTERNATIONAL SEARCHING AUTHORITY					
To: SEMICONDUCTOR ENERGY LABORATORY CO., LTD. 398, Hase, Atsugi-shi, Kanagawa 2430036 Japan		PCT ITTEN OPINION OF THE ONAL SEARCHING AUTHORIT	Y		
Japan		(PCT Rule 43 <i>bis</i> .1)			
		·			
·	Date of mailing (day/month/year)	19. 4. 2005			
Applicant's or agent's file reference PCT7695-7696	FOR FURTHER A	CTION See paragraph 2 below			
International application No. International filing date		Priority date (day/month/year)			
PCT/JP2005/001280 24.01.	.2005	26.01.2004			
International Patent Classification (IPC) or both national classificat	ation and IPC				
Applicant					
SEMICONDUCTOR ENERGY LABORAT	ORY CO., I	TD.			
1. This opinion contains indications relating to the following its					
 This opinion contains indications relating to the following items: Box No. I Basis of the opinion 					
Box No. II Priority		•			
Box No. III Non-establishment of opinion with reg.	ard to novelty inventi	ve sten and industrial applicability	•		
	and to novelty, invent				
	200				
Box No. V Reasoned statement under Rule 43bis. 1(scitations and explanations supporting s		eity, inventive step or industrial applicable	iuty;		
Box No. VI Certain documents cited		· ·			
Box No. VII Certain defects in the international app	lication				
Box No. VIII Certain observations on the internation	al application				
2. FURTHER ACTION		•	. 1		
If a demand for international preliminary examination is ma International Preliminary Examining Authority ("IPEA") excep other than this one to be the IPEA and the chosen IPEA has no opinions of this International Searching Authority will not be	ot that this does not apport of the contractions of the contractio	ly where the applicant chooses an Author	ority		
If this opinion is, as provided above, considered to be a written a written reply together, where appropriate, with amendments, PCT/ISA/220 or before the expiration of 22 months from the process.	before the expiration o	f 3 months from the date of mailing of F			
For further options, see Form PCT/ISA/220.	•				
3. For further details, see notes to Form PCT/ISA/220.			·		
Date of completion of this opinion 30.03	.2005				
Name and mailing address of the ISA/JP	Authorized officer	4L 93	61		
Japan Patent Office	KAZUNARI				

3-4-3, Kasumigaseki, Chiyoda-ku, Tokyo 100-8915, Japan Telephone No. +81-3-3581-1101 Ext. 3498

International application No.
PCT/JP2005/001280

Box	No. I	Basis of the opinion
1.	With r	egard to the language, this opinion has been established on the basis of the international application in the language in
		it was filed, unless otherwise indicated under this item.
		This opinion has been established on the basis of a translation from the original language into the following language, which is the language of a translation furnished for the purposes of international search (under
	1	Rules 12.3 and 23.1(b)).
	•	
2.		egard to any nucleotide and/or amino acid sequence disclosed in the international application and necessary to the linvention, this opinion has been established on the basis of:
	a. type	of material
		a sequence listing
		table(s) related to the sequence listing
	b. form	nat of material in written format
		in computer readable form
-	c. time	of filing/furnishing
	늗	contained in the international application as filed. filed together with the international application in computer readable form.
	. \vdash	furnished subsequently to this Authority for the purposes of search.
	L	
3.		In addition, in the case that more than one version or copy of a sequence listing and/or table relating thereto has been filed or furnished, the required statements that the information in the subsequent or additional copies is identical to that
		in the application as filed or does not go beyond the application as filed, as appropriate, were furnished.
4.	Addit	ional comments:
		•
	• .	

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Box No.	Non-establishment of opinion with regard to novelty, inventive step and industrial applicability
	stions whether the claimed invention appears to be novel, to involve an inventive step (to be non obvious), or to be industrially ble have not been examined in respect of:
	the entire international application
\square	claims Nos. 27
becau	nce·
	the said international application, or the said claims Nos relate to the following subject matter which does not require an international preliminary examination (specify):
,	
	the description, claims or drawings (indicate particular elements below) or said claims Nos are so unclear that no meaningful opinion could be formed (specify):
	the claims, or said claims Nos are so inadequately supported by the description that no meaningful opinion could be formed.
	by the description that no meaningful opinion could be formed.
\checkmark	no international search report has been established for said claims Nos. 27
	the nucleotide and/or amino acid sequence listing does not comply with the standard provided for in Annex C of the Administrative Instructions in that:
	the written form has not been furnished
	does not comply with the standard
	the computer readable form has not been furnished
	does not comply with the standard
	the tables related to the nucleotide and/or amino acid sequence listing do not comply with the technical requirements provided for in Annex C-bis of the Administrative Instructions in that the computer readable form:
•	has not been furnished
	does not comply with the technical requirements
	See Supplemental Box for further details.

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Box No. IV	Lack of unity of invention
1. 🚺 In resp	ponse to the invitation (Form PCT/ISA/206) to pay additional fees the applicant has:
\checkmark	paid additional fees
	paid additional fees under protest
	not paid additional fees
لــــــا	
	authority found that the requirement of unity of invention is not complied with and chose not to invite the applicant to iditional fees.
3. This Author	prity considers that the requirement of unity of invention in accordance with Rule 13.1, 13.2 and 13.3 is
com	plied with
✓ not	complied with for the following reasons:
"form formi formi film a las havin the m disch micro those inven	"special technical feature" of claims 1-26 relates to ing a first film pattern by a droplet discharge method; ng a photosensitive material over the first film pattern; ng a mask pattern by irradiating a region where the first pattern and the photosensitive material are overlapped with er beam by developing; and forming a second film pattern g a desired shape by etching the first film pattern using ask pattern as a mask", while the "special technical re" of claims 28-31 relates to "a wiring formed by a droplet arge method and a gate electrode which has a width of 5 meters or less". There is no technical relationship among inventions involving one or more of the same or sponding technical features. Therefore, these groups of tions are not so linked as to form a single general tive concept.
4. Conseque	ently, this opinion has been established in respect of the following parts of the international application:
	parts.
<u></u>	parts relating to claims Nos. 1-26, 28-31

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Statement			
Novelty (N)	Claims	1-26	YES
	Claims	28-31	NO
Inventive step (IS)	Claims	1-14,16,21	YES
	Claims	15,17-20,22-26,28-31	NO
Industrial applicability (IA)	Claims	1-26,28-31	YES
	Claims		NO

2. Citations and explanations

D1:JP 2002-313226 A(FUJITSU LIMITED), 2002.10.25, [0021], Fig. 2, (Family:none) D2:JP 11-254237 A(SEIKO EPSON CORPORATION), 1999.09.21, [0020]-[0025], (Family:none)

D3:JP 2003-258265 A(NATIONAL INSTITUTE OF ADVANCED INDUSTRIAL SCIENCE AND TECHNOLOGY), 2003.09.12, [0032]-[0035], (Family:none) D4:JP 2001-179167 A(NEC CORPORATION), 2001.07.03, [0010]-[0018], (Family:none)

Claims 1-14

The subject matters of claim 1-14 are considered to involve an inventive step over the document cited in the international search report.

D1, D2, D3 and D4 do not disclose a method for manufacturing a thin film transistor comprising the steps of: forming a semiconductor film by a droplet discharge method, forming a photosensitive material over the semiconductor film, forming a second mask pattern by irradiating the photosensitive material with a laser beam and by developing, forming a semiconductor region having a desired shape by etching the semiconductor film using the second mask pattern as a mask. And the subject matters claimed appear to be non-obvious.

Claims 15, 17-20, 22-26

The subject matter of claim 15, 17-20, 22-26 does not appear to involve an inventive step in view of the D1 and D2 cited in the ISR.

D1 discloses a method for manufacturing a semiconductor device, comprising the steps of: forming a semiconductor film, forming a photosensitive material over the semiconductor film, forming a second mask pattern by irradiating the photosensitive material with a beam and by developing, forming a semiconductor region having a desired shape by etching the semiconductor film using the second mask pattern as a mask. And D2 discloses a step of forming a first pattern by a droplet discharge method. The method for manufacturing a pattern in D1 and D2 are concerned with mutually related technical fields. Therefore, the skilled person in the art would easily conceive the idea of applying the technical feature employed in D2 to the invention disclosed in D1.

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Supplemental Box

In case the space in any of the preceding boxes is not sufficient. Continuation of: $V \cdot 2$

Claim 16

The subject matter of claim 16 is considered to involve an inventive step over the document cited in the international search report.

D1, D2, D3 and D4 do not disclose a step forming a third film pattern to be connected to the second film pattern by a droplet discharge method. And the subject matter claimed appears to be non-obvious.

Claim 21

The subject matter of claim 21 is considered to involve an inventive step over the document cited in the international search report.

D1, D2, D3 and D4 do not disclose that the third film pattern is a wiring. And the subject matter claimed appears to be non-obvious.

Claims 28-31

The subject matters of claim 28-31 do not meet the requirement of novelty. D3 discloses a gate electrode which has a width of 5 micron or less and gate wiring is formed by a droplet discharge method.